This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1   1. – 6.   (Cancelled)

1   7.   (Currently Amended)   A method of manufacturing an
2   integrated circuit, the method comprising:
3   providing a pattern of radiation via an LCD or LED assembly
4   in response to a control signal from a computer, the computer generating
5   the control signal in response to image data stored in a database, the
6   computer ~~generating~~ executing software to select a component, and
7   generating ~~data from the image data to generate~~ the control signal from
8   the image data associated with the component; and
9   performing a semiconductor fabrication process in
10   accordance with the pattern of radiation.

1   8.   (Original)   The method of claim 7, further comprising:
2   providing a second pattern of radiation via the LCD or LED
3   assembly; and
4   performing a second semiconductor fabrication process in
5   accordance with the second pattern of radiation.

1   9.   (Original)   The method of claim 7, wherein the pattern is
2   provided to a wafer in a step and repeat process.

1   10.   (Original)   The method of claim 7, wherein the pattern is
2   representative of a metal layer associated with the integrated circuit.

1   11.   (Original)   The method of claim 7, wherein the pattern is
2   representative of a structure associated with a transistor for the integrated
3   circuit.

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1   12.   (Previously Amended)   The method of claim 7, wherein a

2 the component data is related to interconnect layers.

1   13.   (Original)   The method of claim 7, wherein the integrated

2 circuit is an ASIC.

1   14.   (Original)   The method of claim 7, wherein the pattern is

2 provided via the LCD assembly.

1   15. - 20.   (Cancelled)

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1   21.   (Currently Amended)   A method of using a pattern

2 generator for an integrated circuit fabrication system, the method

3 comprising:

4   providing a pattern of radiation via an LCD assembly in

5 response to a control signal from a computer, the computer generating the

6 control signal in response to image data stored in a database, the

7 computer executing software to select a ~~generating~~ component ~~data from~~

8 ~~the image data to generate~~ and generating the control signal from the

9 image data associated with the component; and

10   performing a semiconductor fabrication process in

11 accordance with the pattern of radiation.

1   22.   (Previously Added) The method of claim 21, wherein the

2 pattern is for an ASIC device.

1   23.   (Previously Added) The method of claim 22, wherein in the

2 pattern generator further comprises:

3   means for providing a pattern of light;

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4   means for controlling the means for pr viding, wherein the

5   means for controlling selects the pattern; and

6   means for focusing the light on a wafer.

1   24.   (Previously Added) The method of claim 15, wherein the

2   image data are shapes representing component interconnects.

1   25.   (Previously Added) The method of claim 23, wherein the

2   means for controlling includes a workstation executing a software

3   program.

1   26.   (Previously Added) The method of claim 25, wherein the

2   means for providing a pattern includes liquid crystals.

1   27.   (Currently Amended)   In a lithographic system for an

2   integrated circuit fabrication process, the lithographic system including a

3   computer and a configurable mask or reticle coupled to the computer,

4   wherein the configurable mask or reticle allows light to be transmitted in a

5   pattern controlled by a control signal from the computer, a method

6   comprising:

7   providing a pattern of radiation via the configurable mask or

8   reticle in response to a control signal from a computer, the computer

9   generating the control signal in response to image data stored in a

10   database, the computer ~~using~~ executing software to select a component

11   ~~data from the image data~~ to generate the control signal in response to the

12   image data associated with the component; and

13   performing a semiconductor fabrication process in

14   accordance with the pattern of radiation.

1   28.   (Previously Added) The method of claim 27, wherein the

2   configurable mask or reticle is an LCD or LED matrix.

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cont.

1   29.   (Previously Added) The method of claim 27 wherein the
2   image data includes ASIC information.

1   30.   (Previously Added) The method of claim 29, wherein the
2   database is stored on a storage media.

1   31.   (Previously Added) The method of claim 27, wherein the
2   image data is related to transistor structures.

1   32.   (Previously Added) The method of claim 27, wherein the
2   control signal is a video signal.

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